CHEMICAL HERITAGE FOUNDATION

ELSA REICHMANIS

Transcript of an Interview
Conducted by

David C. Brock

at

Murray Hill, New Jersey

on

1 August 2001

(With Subsequent Corrections and Additions)

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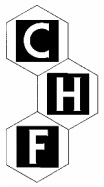

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ELSA REICHMANIS

1953 Born in Melbourne, Australia on 9 December

Education

1972 B.S., chemistry, Syracuse University
1975 Ph.D., organic chemistry, Syracuse University

Professional Experience

Syracuse University
1972 Organic Chemistry Teaching Assistant
1973-1975 Research Fellow
1975-1976 Postdoctoral Intern
1976-1978 Dr. Chaim Weizmann Fellow

AT&T Bell Laboratories
1978-1984 Technical Staff, Organic Chemistry Research and Development Department
1984-1994 Supervisor, Radiation Sensitive and Applications Group
1994-1995 Head, Polymer and Organic Materials Research Department

Bell Laboratories, Lucent Technologies
1996-present Director, Polymer and Organic Materials Research Department

Honors

1972 Phi Beta Kappa
1992 R&D 100 Award, Research and Development Magazine
1993 Society of Women Engineers Achievement Award
1995 Elected to the national Academy of Engineering
1995 AT&T Bell Laboratories Fellow
1996 ASM International Engineering Materials Achievement Award
1997 Elected Fellow of the American Association for the Advancement of Science
1998 Photopolymer Science and Technology Award
1999 ACS Award in Applied Polymer Science
2001 Perkin Medal, Society of Chemical Industry
2001 George Arents Pioneer Medal, Syracuse University

ABSTRACT

Elsa Reichmanis begins the interview with a description of her family's immigration to the United States and her childhood years in Syracuse, New York. Reichmanis developed an interest in chemistry after taking a high school chemistry course. After graduating a year early from high school, Reichmanis enrolled at Syracuse University. While obtaining her B.S. in chemistry, Reichmanis performed heteroaromatic chemistry research in Apostolos G. Anastassiou's laboratory. Completing her degree in three years, Reichmanis decided to remain at Syracuse University for her Ph.D. Upon matriculation, Reichmanis took a technical staff position at AT&T Bell Laboratories, which is currently known as Bell Labs, Lucent Technologies, where she still remains. Reichmanis' work has focused on deep-UV lithography, such as the creation of 248 nm and 193 nm resist technologies. Currently, Reichmanis is performing photonic research. While at Bell Labs, Reichmanis has held numerous positions ranging from technical staff to supervisor to director. Reichmanis concludes the interview with a discussion of Valerie J. Kuck's research on women in chemistry, the definition of innovation, and the future of chemistry.

INTERVIEWER

David C. Brock is Program Manager for Educational and Historical Services at the Chemical Heritage Foundation in Philadelphia. He is currently a Ph.D. candidate in the History Department, Program in the History of Science at Princeton University. In 1995, Mr. Brock received his M.A. in the History of Science from Princeton University, and in 1992, he earned a M.Sc. in the Sociology of Scientific Knowledge from the University of Edinburgh.

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